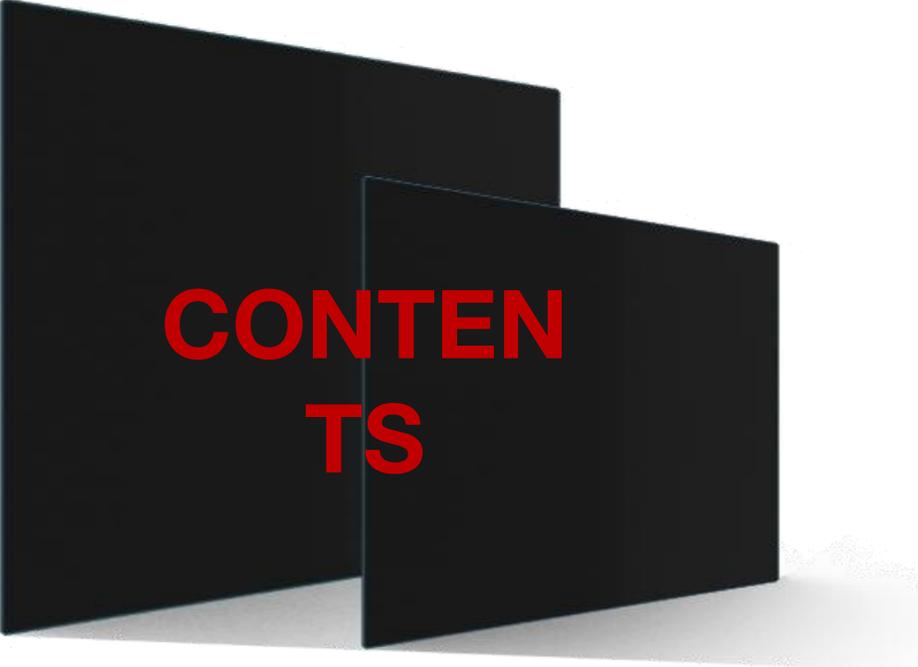


# Laser Process for Next-Gen Solar Cells

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STC India, New Delhi, Feb. 5, 2026



**CONTENTS**

**01**

**Company Overview**

**02**

**Business Landscape**

**03**

**Laser Products for PV**

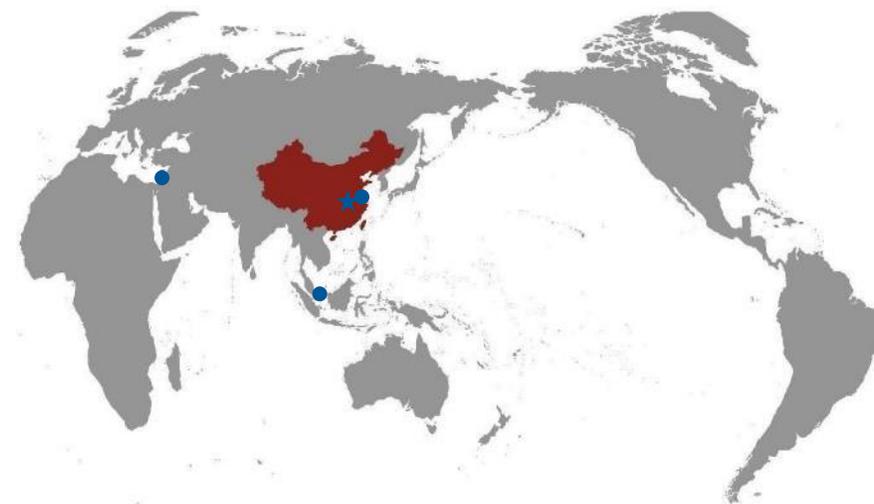
**04**

**Q&A**

# The Company

## DR Laser Technology Corp., Ltd

DR Laser (300776. SZ) is a high-tech enterprise committed to developing advanced technologies for laser applications, focusing on the photovoltaic, next-gen. display, and semiconductor industries. It provides customized solutions integrating design, R&D, and manufacturing for high precision laser processing equipment. Founded in 2008, it is based in Wuhan, the geographic center of China, and it currently has a manufacturing base in Wuxi and global R&D centers in Tel Aviv, Israel, and Singapore.



**Wuhan Headquarter**  
Settled in April 2022



**Wuxi R&D and Manufacturing Base**  
Operated in January 2022



**Israel R&D Center**  
Established in April 2020

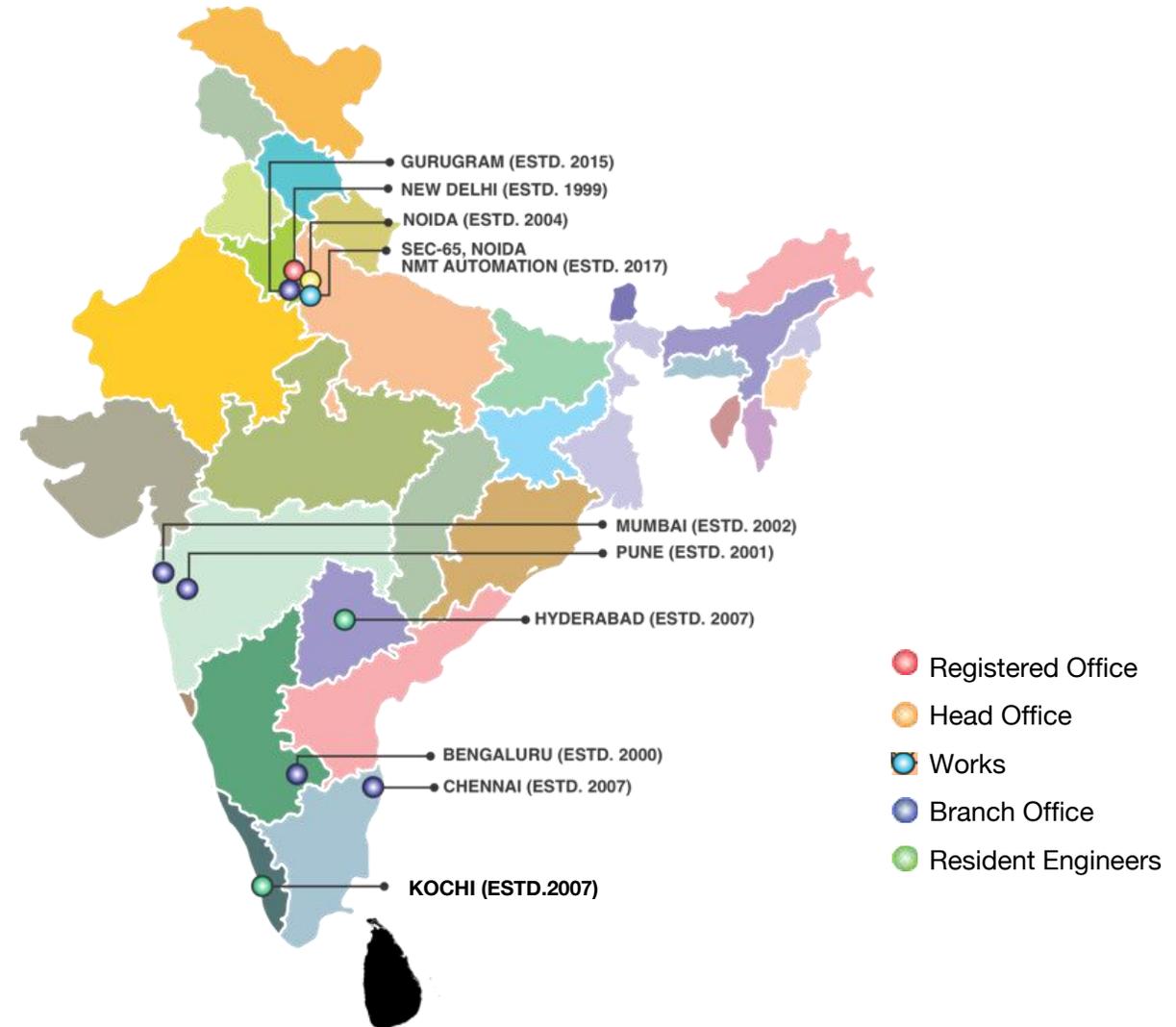


**Singapore R&D Centre**  
Established in January 2022

## NMTronics India Pvt Ltd

- NMTronics is 26 years old Premier Sales & Service company working on Advanced Technologies [SMT, AUTOMATION, & SOLAR]
- Working in Solar industry since 2010 with Industry leading Solar Cell and Module Manufacturing companies
- Strong Service network in India with offices at Noida (HQ), Gurugram, Chennai, Bangalore, Mumbai, Pune, & service representatives in Hyderabad, Kolkata, Jaipur, Ahmedabad, Kochi & Bangladesh
- Joint Human resource of over 400+ trained engineers providing 24x7 support to valued customers
- Engineering Establishment of over 20,000 sq ft in Special Economic Zone [SEZ] for catering to major electronics manufacturers & PV customers
- Manufacturing of Custom automation & standard conveyor system in Noida

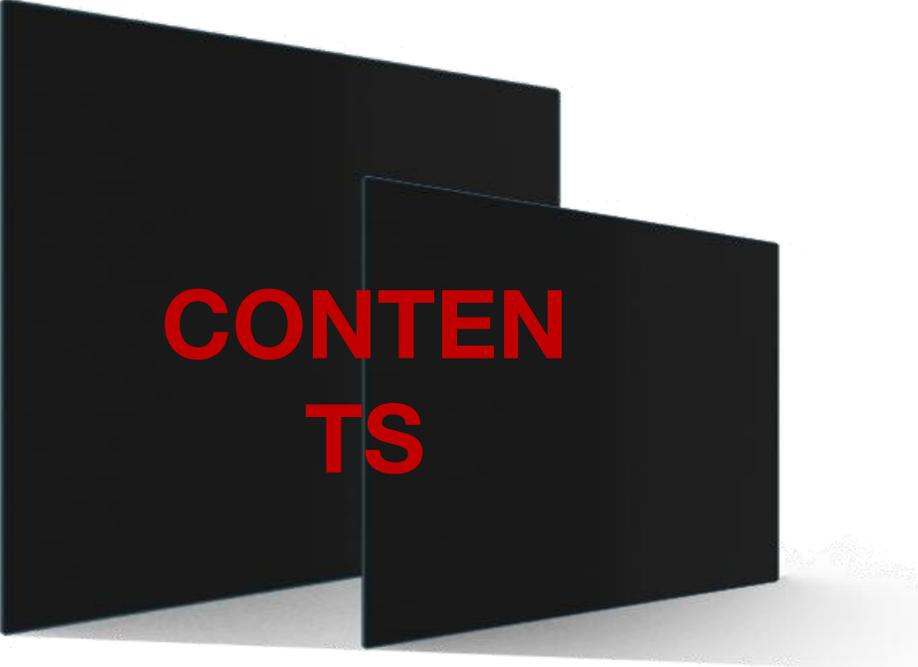
## NMTronics Operations



# Global Market Supported by DR Laser



- LONGi 隆基 Aikosolar JA SOLAR 通威太阳能 TV SOLAR Trinasolar 天合光能 CanadianSolar Jinko ASTRONERGY JTPV SolarSpace 英发睿能 YINGFA RUINING 一造新能 DASOLAR 东磁光伏 DMEGC 东磁光伏 risen solar technology 中束股份 JOLYWOOD RUNERGY 协鑫 GCL
- 平煤隆基 PING MEI LONG JI TCL SOLAR 环晟光伏 HUANSHENG SOLAR CHG 中環控股集团 M-Cells 鸿禧光伏 SunSync 和光同程 SUNREV 新霖飞能科 GPPV JINERGY SUNTECH 尚德电力 SF-PV YINGLI SOLAR 日托光伏 旭合科技 Solar Plus 中国节能 南玻集团 百达 BAIDA HONGRUN 宏润光伏 Redrolar
- SJET 仕淨科技 FuturaSun 润马光能 林洋 LINYANG CNBM Visionary Green Energy Scenery 潞安集团 LÜAN GROUP ECONESS ENERGY ZSI solar 正奇光能 ETERNAL ENERGY EGING PV RI solar 华东光能 国家电投 SPIC TALESUN AKCOME 爱康科技 阳光中科 SHINA EARTH NEW ENERGY



**CONTEN  
TS**

**01**

Company Overview

**02**

Business Landscape

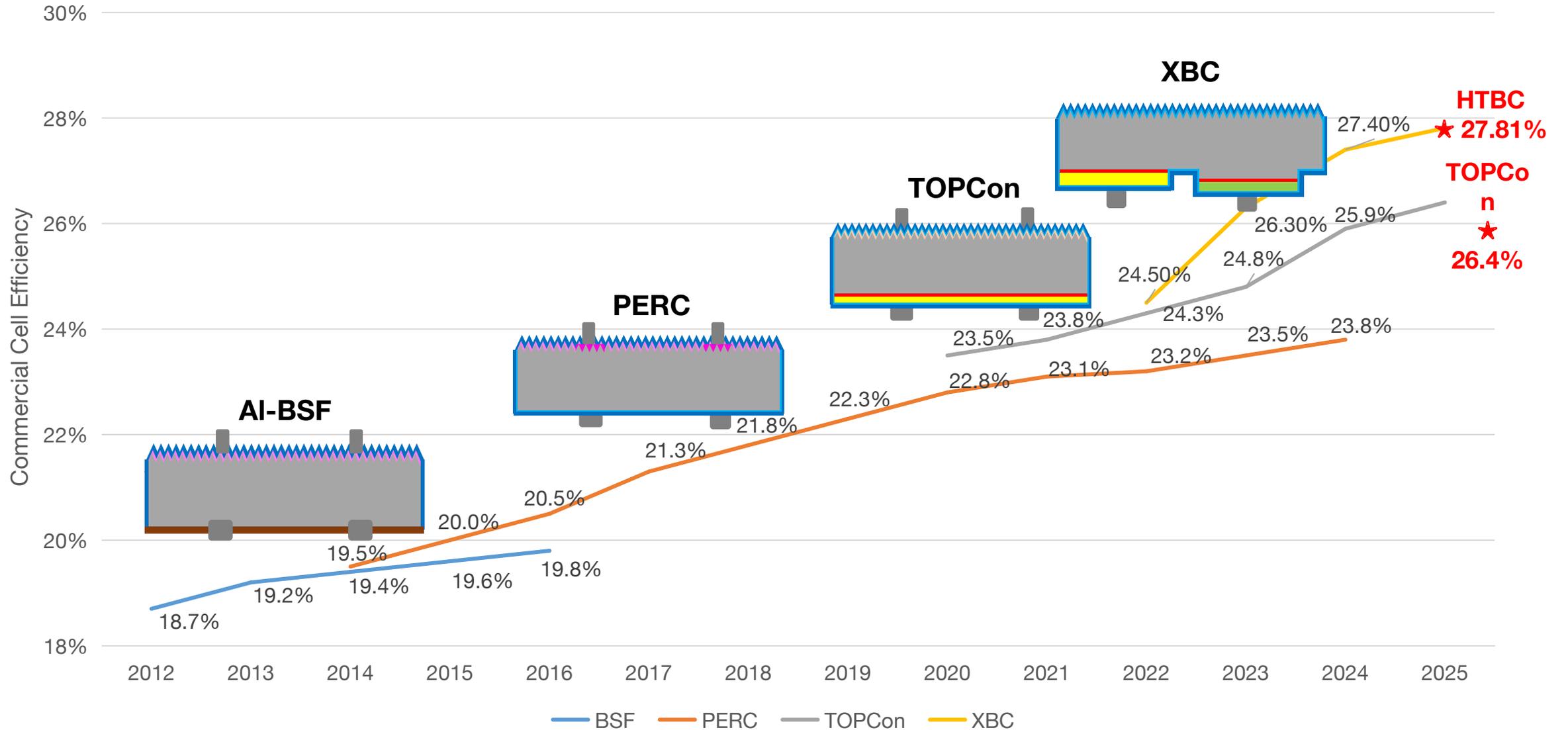
**03**

Laser Products for PV

**04**

Q&A

# Inside World Records of c-Si Solar Cells



# Product Portfolio



Laser Doping for PERC LDSE  
TCI for TOPCon Edge  
Passivation



Laser Ablation for PERC  
LCO



LIF for TOPCon



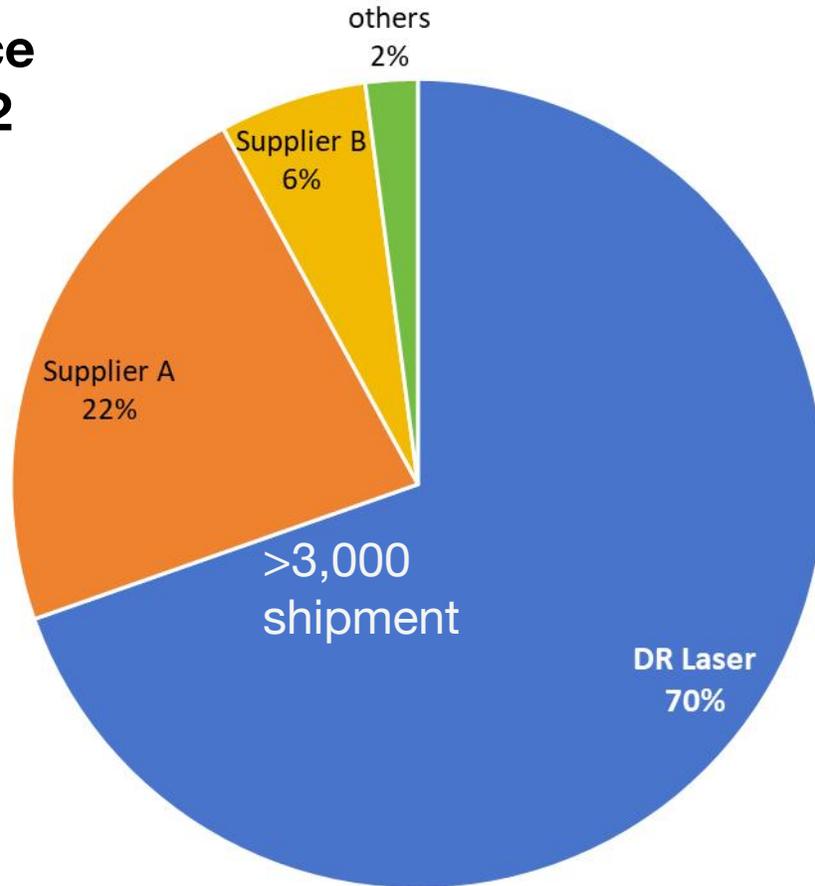
TCSE for TOPCon LDSE  
TCP for TOPCon Poly-Si Fingers  
Laser Processing for XBC



State-of-the-art Metallization Line (PTP/Linear SP) for TOPCon and  
HJT

# Market Share of TOPCon Series Equipment

Since  
2022



**Market Share**

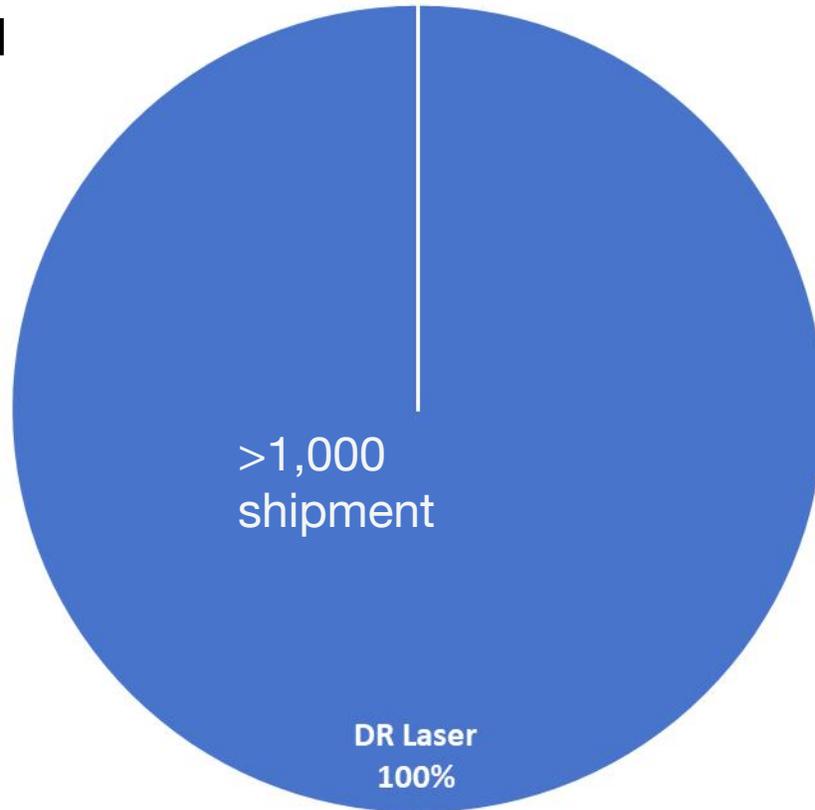
## TOP 15

- TW Solar
- Jinko
- JA Solar
- JTPV
- Trina Solar
- Canadian Solar
- Solar Space
- Astronergy
- DASolar
- Yingfa
- Longi
- Aiko Solar
- GCL
- Sunsync
- TOP Solar

**Customer Portfolio**

# Market Share of XBC Series Equipment

Since  
2021



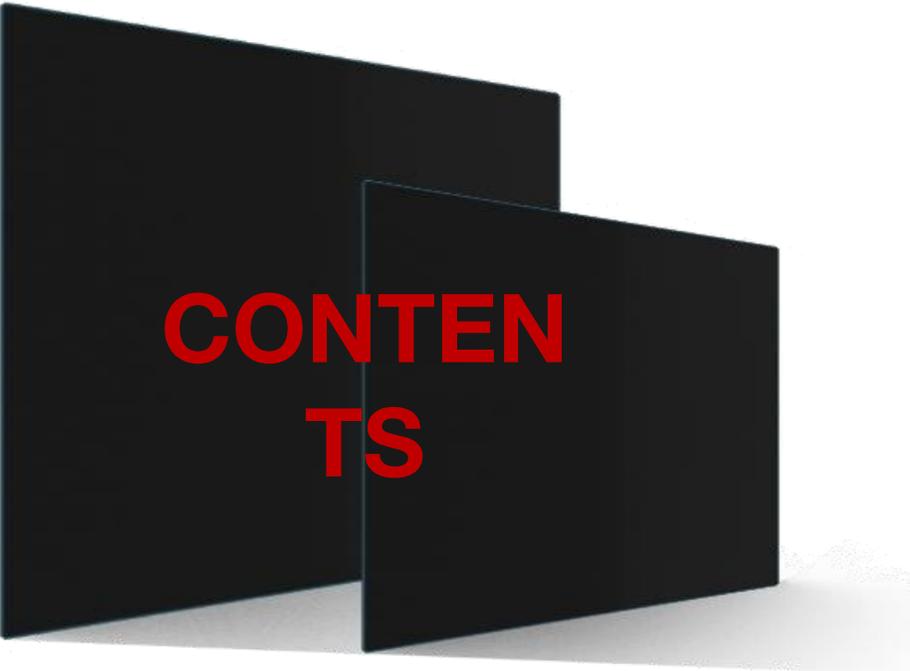
**Market Share**

## TOP 2

- Longi
- Aiko Solar

Cooperating with  
more than 10  
customers

**Customer Portfolio**



**CONTENTS**

01

Company Overview

02

Business Landscape

03

Laser Products for PV

04

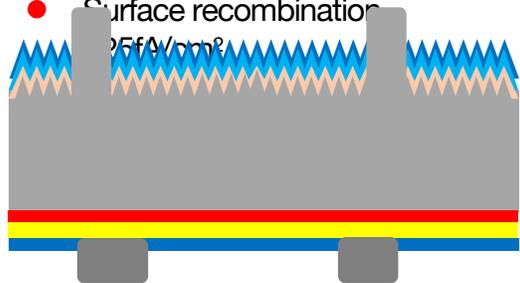
Q&A

# Laser Processing Equipment for TOPCon

# Evolution of TOPCon Cell Technology

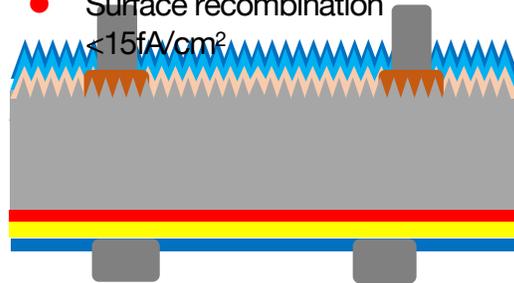
**2022~2023**  
**Gen. 1**  
**24.0~24.5%**

- Tunneling contact on the rear
- Surface recombination  $< 25 \text{ fA/cm}^2$



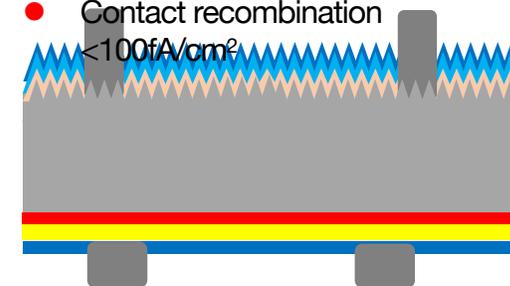
**2023~2024**  
**Gen. 2**  
**24.6~25.0%**

- Laser doped selective emitter
- Surface recombination  $< 15 \text{ fA/cm}^2$



**2024~**  
**Gen. 3**  
**25.1~25.5%**

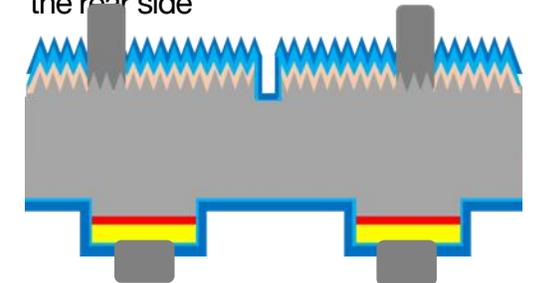
- Laser induced firing
- Contact recombination  $< 100 \text{ fA/cm}^2$



**2025~**

**Gen. 4 >25.5%**

- Laser induced firing
- Laser-ablated edge passivation on the front side
- Laser-based selective tunneling contact on the rear side



Cell Efficiency (%)

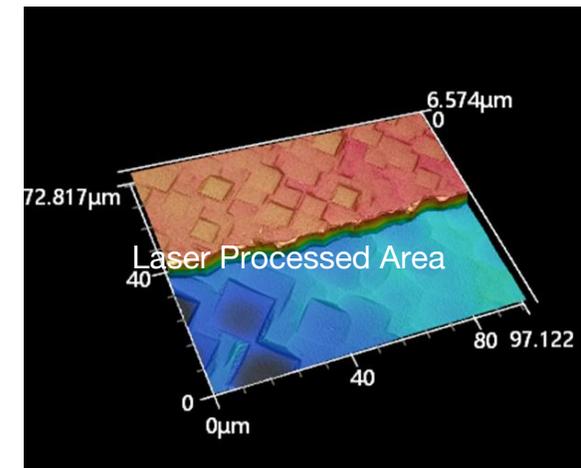
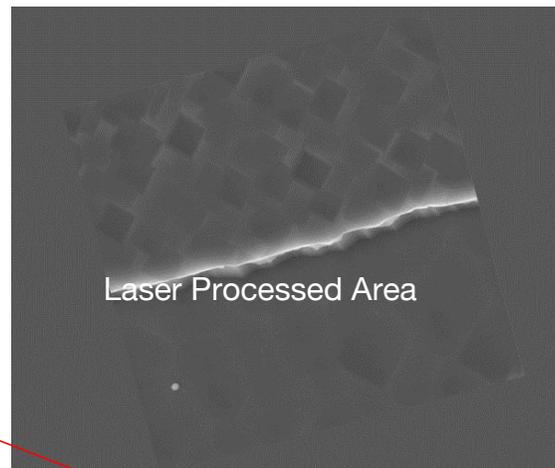
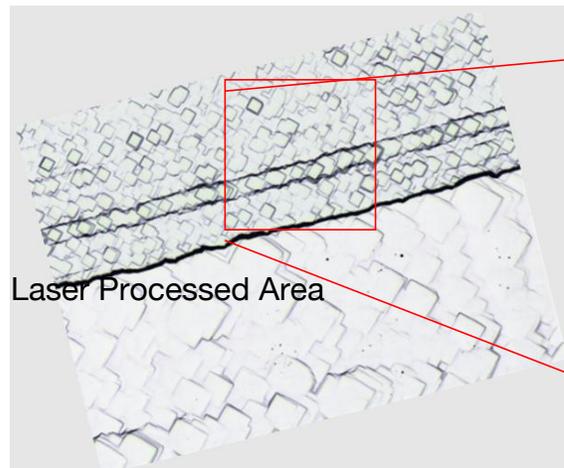
# Gen. 4 – TCP for TOPCon Poly-Si Fingers



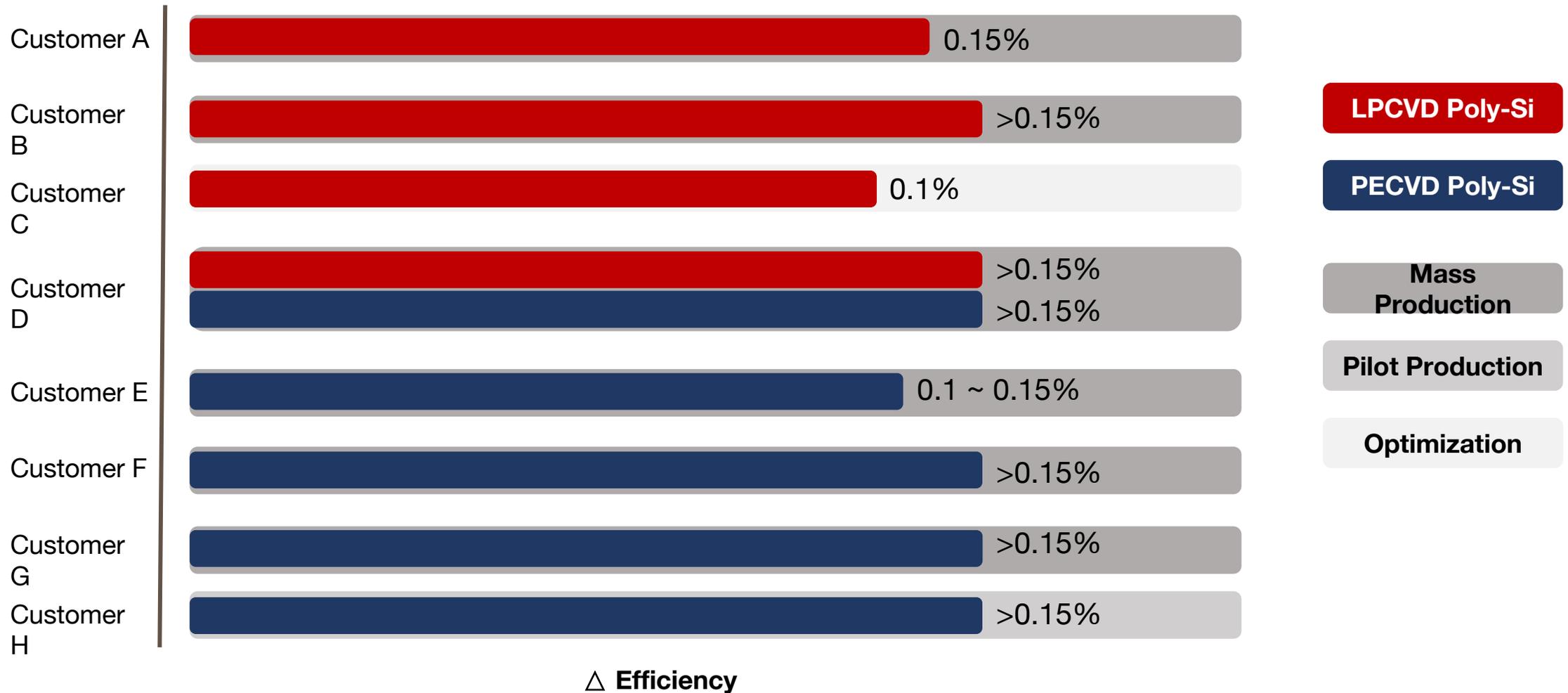
- Dual-lane design with four individual laser sources. No mutual interruption neither in operation or maintenance
- 0.1 ~ 0.15% efficiency gain proven in mass production
- 3~5% bifaciality enhancement proven in mass production
- Throughput up to 9,600UPH (CT<0.75sec) on M10 wafers valid for the varied design of the factories, and the varied wafer sizes including half-cut and rectangle
- Vibration simulation and optimization design from resonance. long-term stability guaranteed

# Something Should Know about Poly-Si Fingers

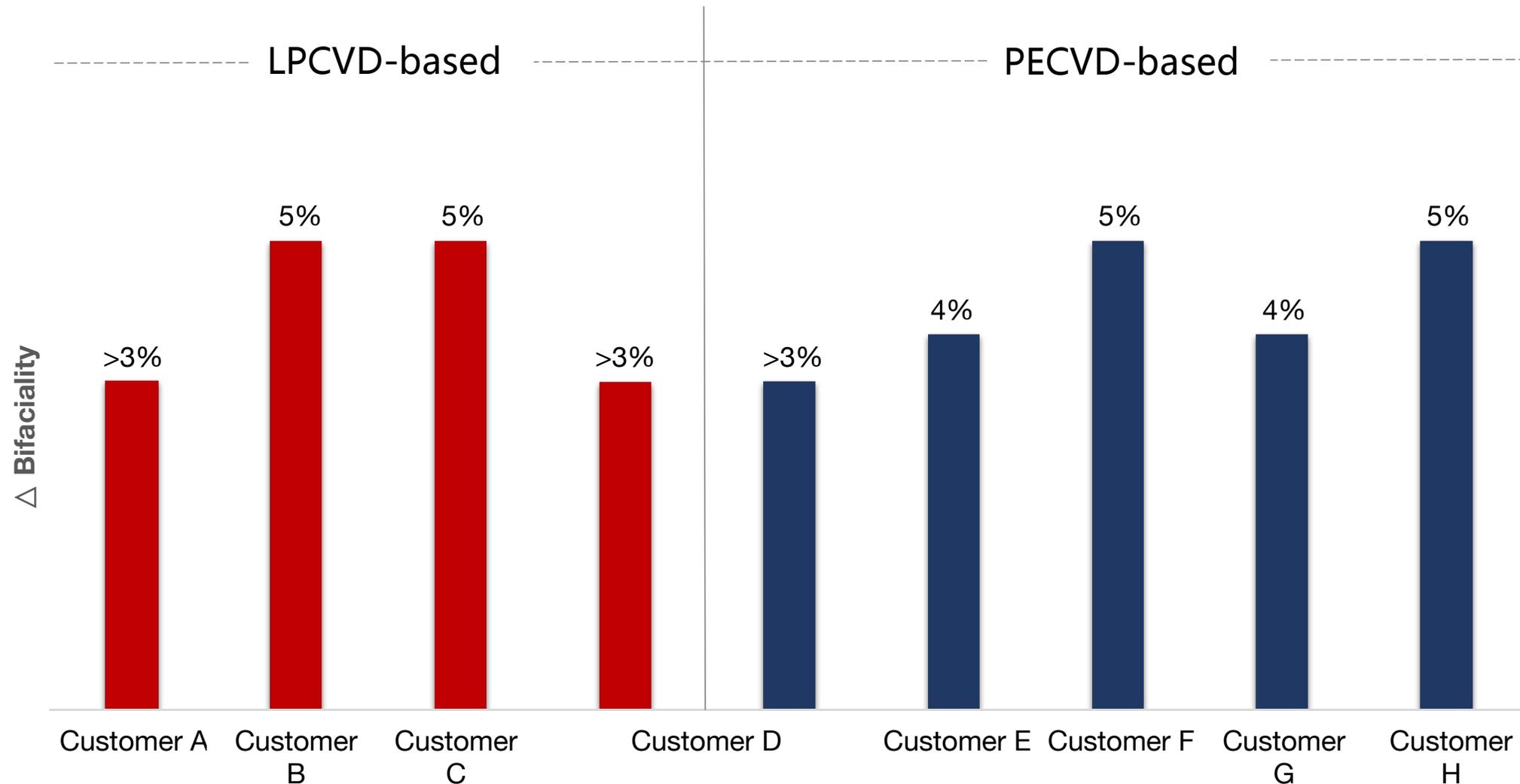
	LPCVD Process	PECVD Process
<b>Poly-Si thickness</b>	120~160 nm	100~130 nm
<b>Doping process</b>	ex-situ doping (POCl3 diffusion)	in-situ doping (annealing)
<b>Capping layer thickness</b>	tens of nm of PSG by diffusion time	tens of nm of SiOx by annealing time
<b>Laser modification process</b>	Low energy density required	High energy density required
<b>Wet etching depth</b>	2 ~ 4 $\mu\text{m}$	5 ~ 7 $\mu\text{m}$
<b>Major enhancement</b>	$I_{sc}$	$V_{oc}$



# Process Performance of Poly-Si Fingers on Cells



# Process Performance of Poly-Si Fingers on Cells



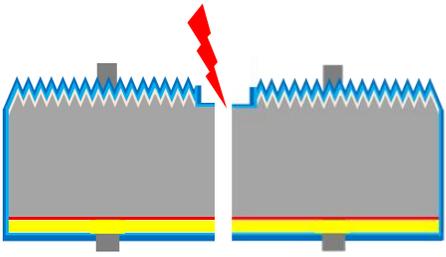
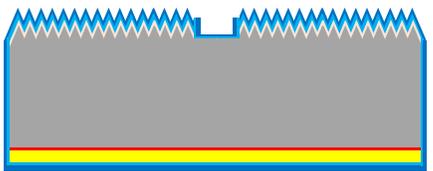
# Gen. 4 – TCI for TOPCon Edge Passivation



- Realizing the edge isolation of p-n junction from the transportation of the carriers to the edge of solar cell causing the recombination by cutting-induced defects
- Most cost-effective approach to realize edge passivation by laser isolation of p/n junction
- Dual-lane design with four individual laser sources. No mutual interruption neither in operation or maintenance
- 300 ~ 500 $\mu$ m line width , compatible with half-cut and multi-cut designs
- Power output of 2382mmX1134mm module can be enhanced by 2 ~ 3W, half-cut cell efficiency can be also enhanced by 0.1 ~0.15%
- Throughput up to 9,000UPH (CT<0.75sec) on M10 wafers valid for the varied design of the factories, and the varied wafer sizes including rectangle

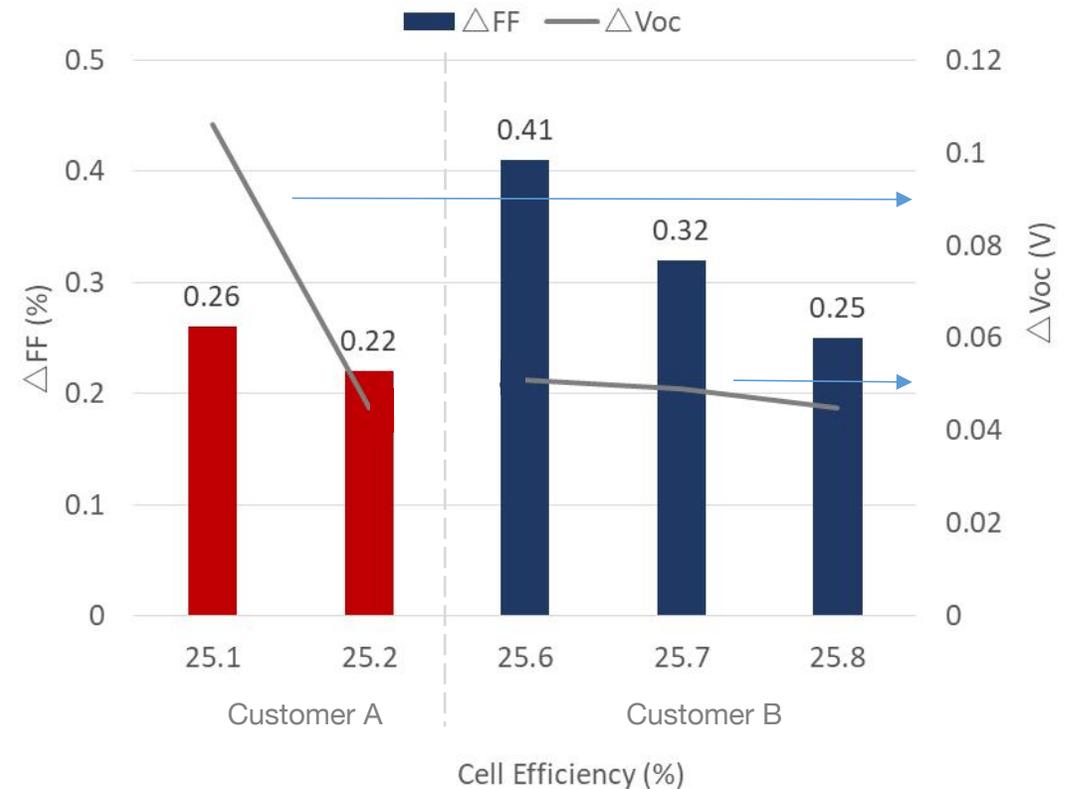
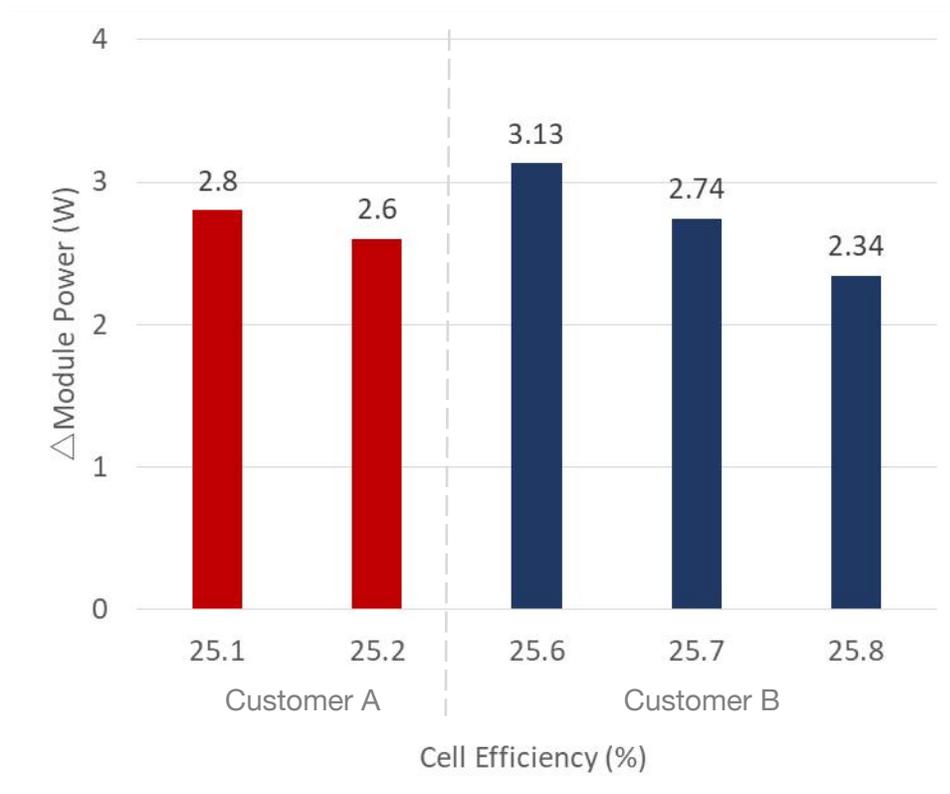
# Process Sequence of the Varied Edge Passivation Approaches

**Most cost-effective approach to realize edge passivation**



Half- or Quard-cutting	Half- or Quard-cutting	Half-cutting	Quard-cutting	Quard-cutting
Texturing	Texturing	Texturing	Texturing	Texturing
Boron Diffusion				
TCI Laser Ablation	TCI Laser Ablation		TCI Laser Ablation	
Rear Polishing				
Al <sub>2</sub> O <sub>3</sub> Deposition				
SiN <sub>x</sub> Deposition				
Metallization	Metallization	Metallization	Metallization	Metallization
	Testing (full cell)	Testing (full cell)	Testing (full cell)	Testing (full cell)
	Laser Cutting	Laser Cutting	Laser Cutting	Laser Cutting
		EPD	EPD	EPD
				EPD
Testing & Sorting				
Laser Cutting				

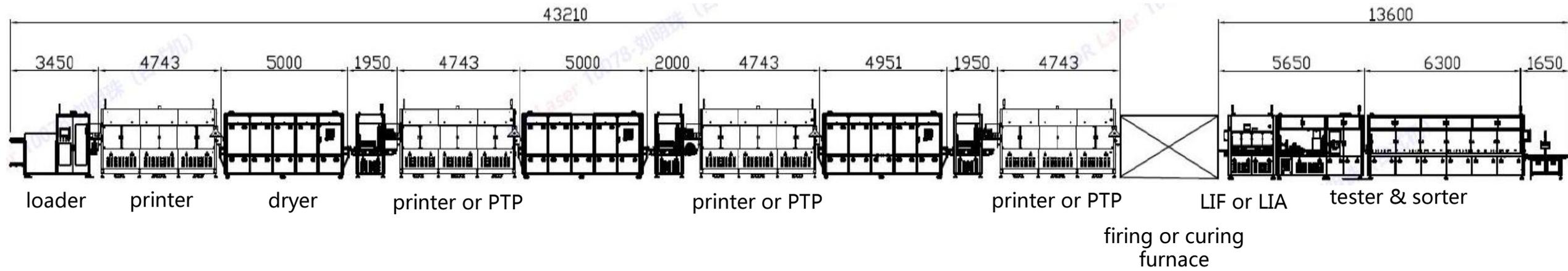
# Process Performance of TCI Edge Passivation



Remark : Customer A , 182mm\*183.75mm , 72 cells , half cutting , 2278\*1134mm module ;  
Customer B , 182mm\*210mm , 66 cells , half cutting , 2382\*1134mm module

# State-of-the-art Metallization Solution

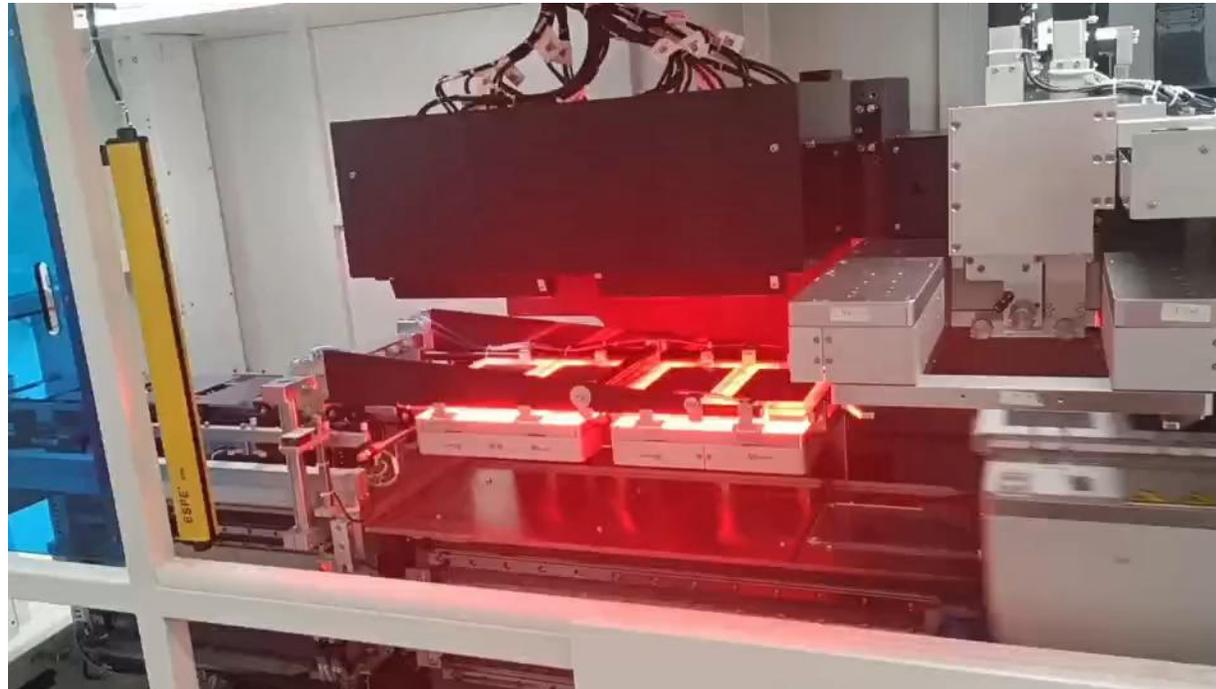
- The State-of-the-art metallization line launched in 2025 including pattern transfer printing (PTP), screen printing, laser induced firing (LIF) or laser induced annealing (LIA), and tester & sorter



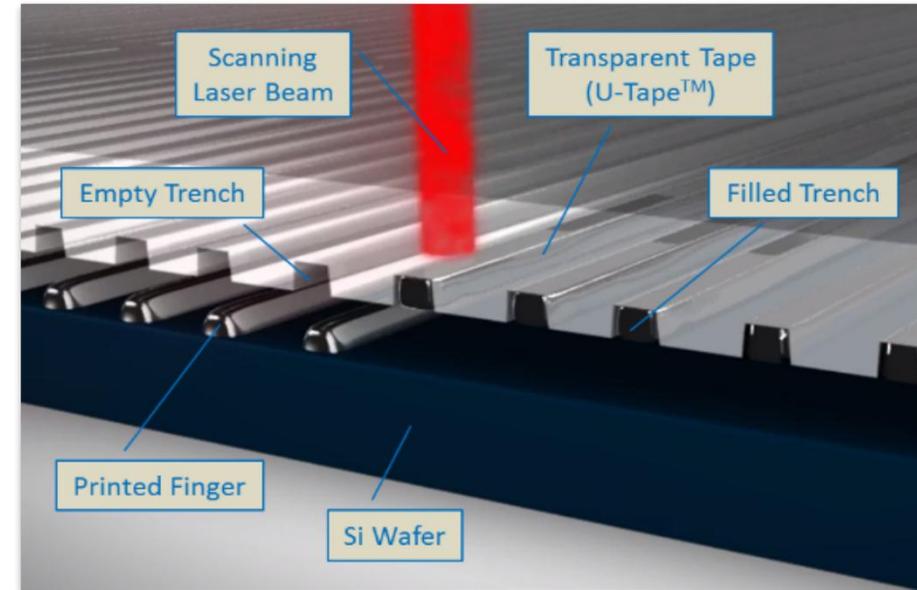
# Linear Reciprocation Screen Printing

**High throughput and high alignment accuracy realized by the design of linear reciprocation**

- Throughput
  - ≥9500pcs/h (CT≤0.76s) on M10, ≥8000pcs/h (CT≤0.9s) on G12
  - ≥16000pcs/h (CT≤0.45s) on half-cut M10, ≥15000pcs/h (CT≤0.48s) on half-cut G12
- Pattern alignment accuracy ±6μm

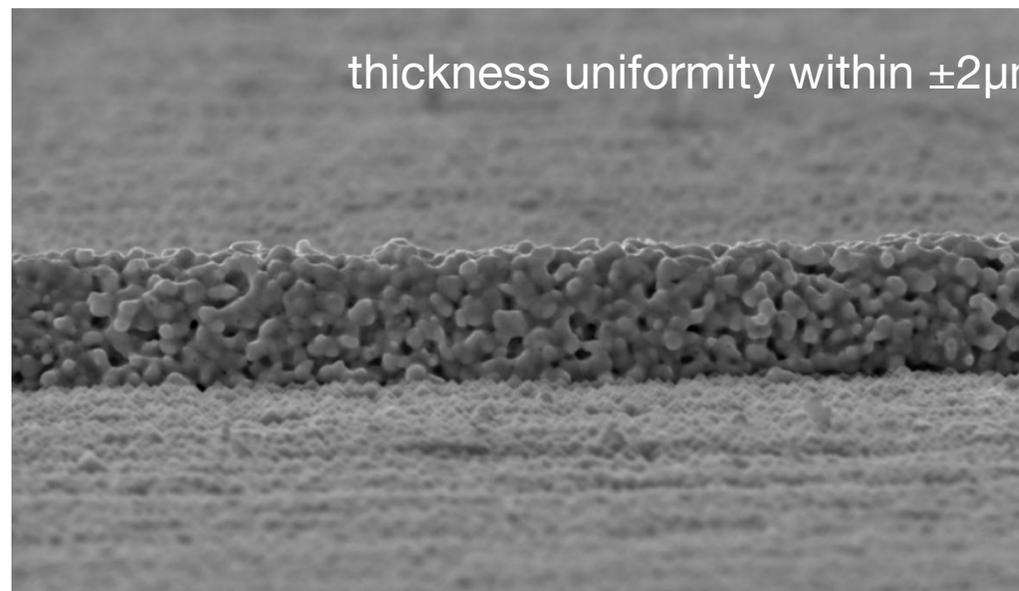
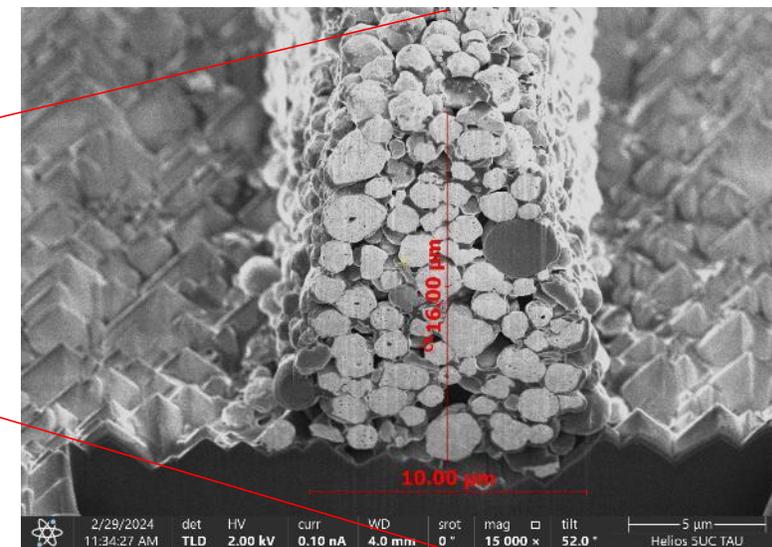
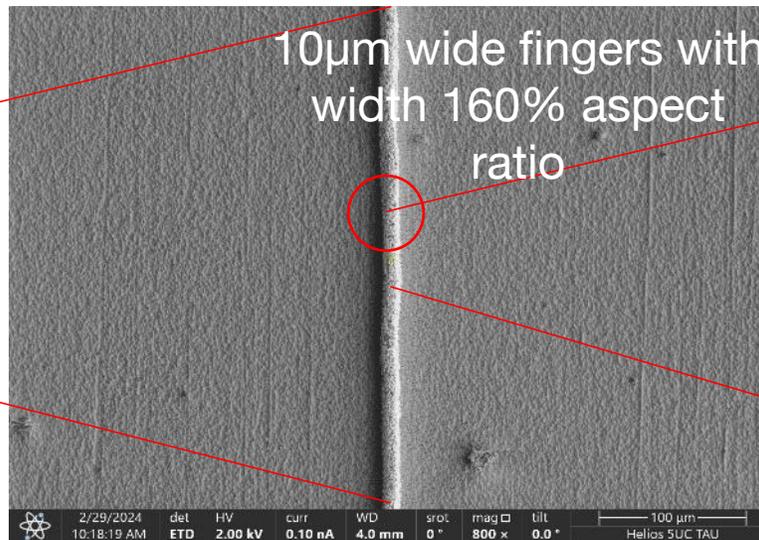
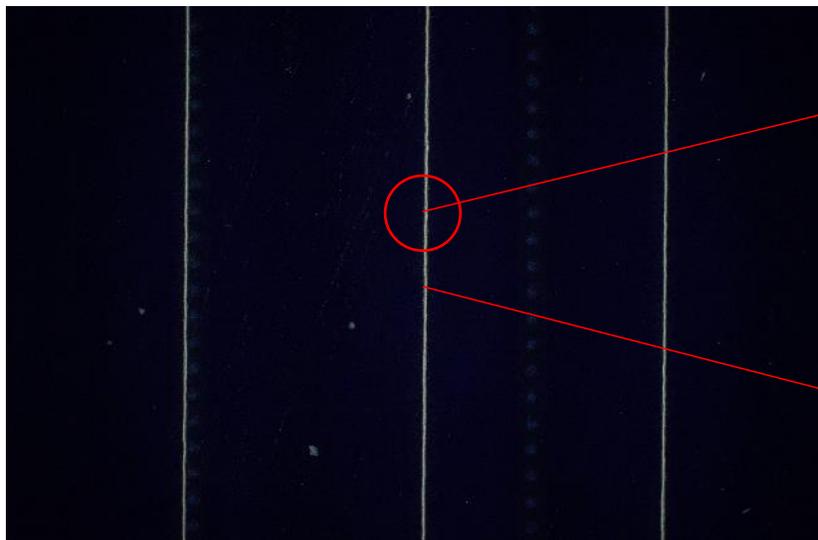


# PTP (Pattern Transfer Printing) for Metallization



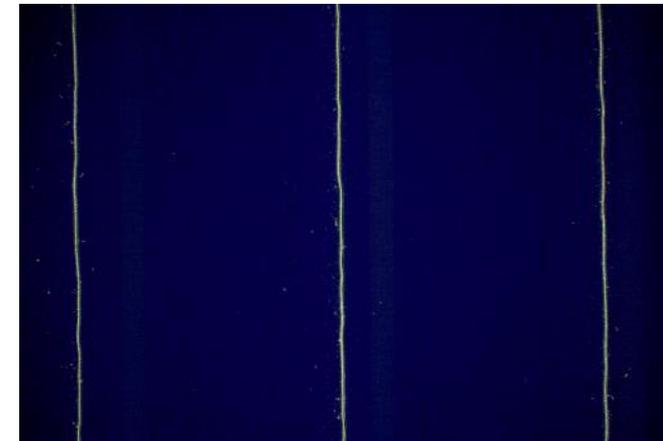
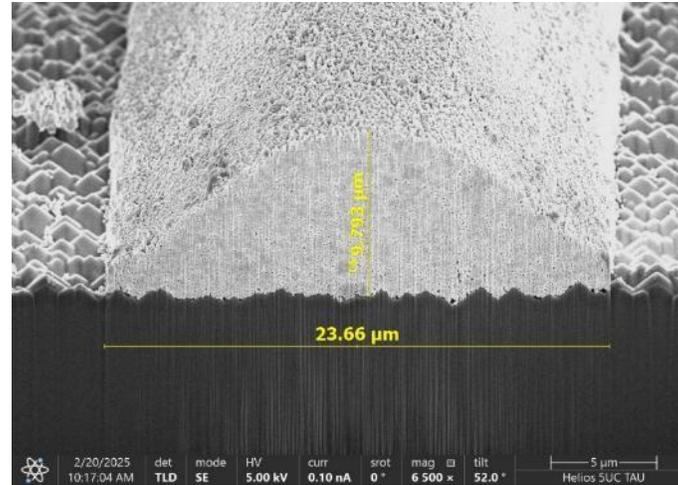
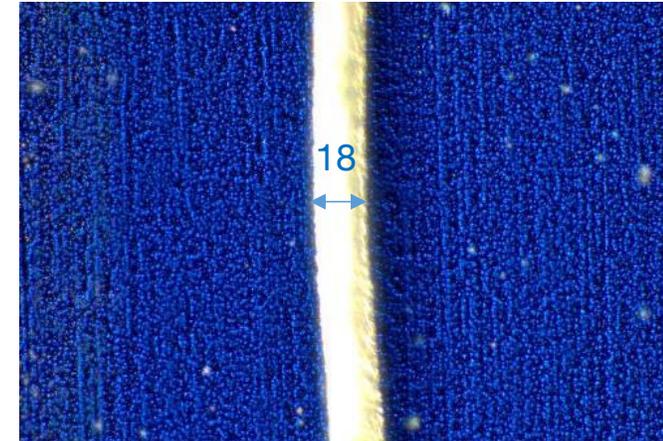
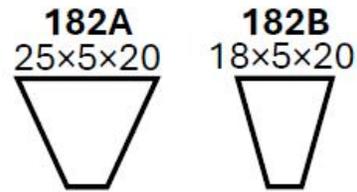
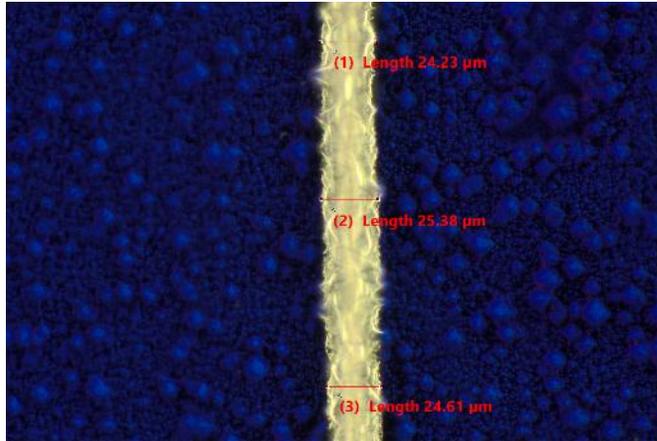
- Printing width  $\geq 10\mu\text{m}$ , 10 to  $>100\%$  aspect ratio adjustable
- Fine fingers increasing light absorption area enhance cell efficiency, thin rear fingers reduce paste consumption
- Thickness uniformity of fingers within  $\pm 2\mu\text{m}$
- Non-contact printing process, friendly to ultra-thin

# PTP for TOPCon Metallization



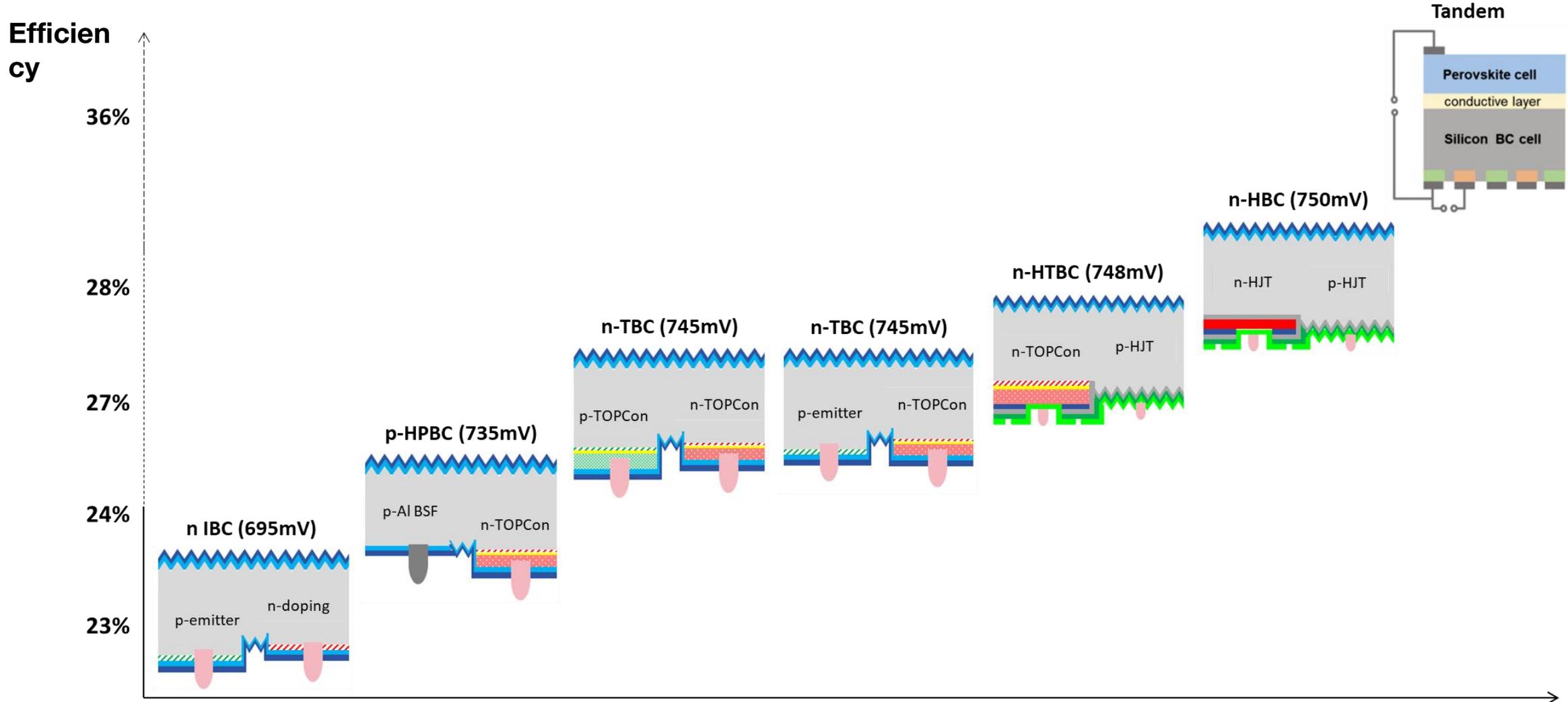
# PTP for Advanced Printing Capabilities

- <20μm fingers printing demonstrated with the cooperation of the leading brands of **Cu** pastes



# Laser Processing Equipment for XBC

# Back-Contact Technology Roadmap

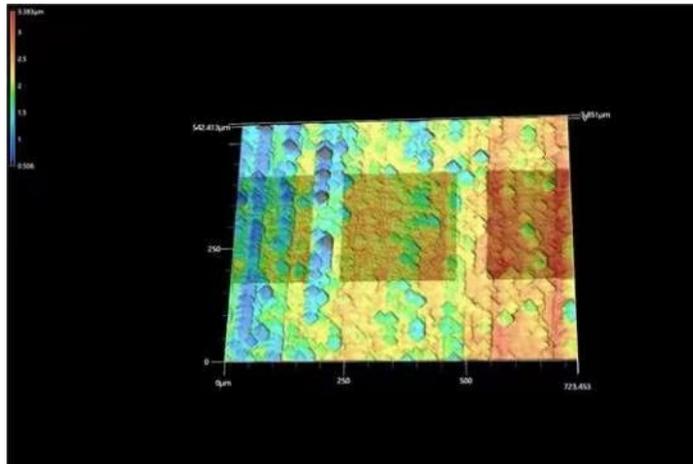


● BC is the ultimate architecture of high-eff. c-Si solar cell by its higher V<sub>OC</sub> and lower shading loss

# Cutting-Edge Laser Patterning for XBC Cells

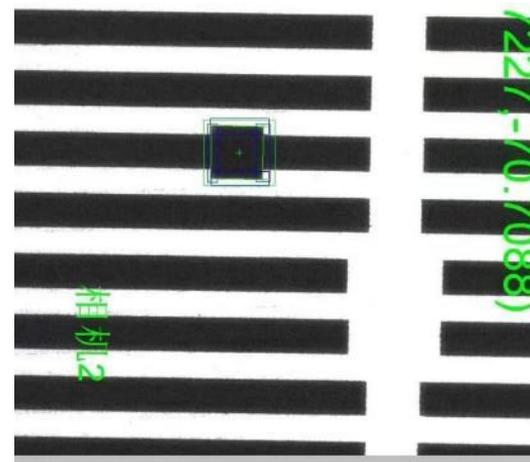
## Large-spot ablation

- Uniform energy distribution over large spot size than ever
- Stable energy management of flat-top spot



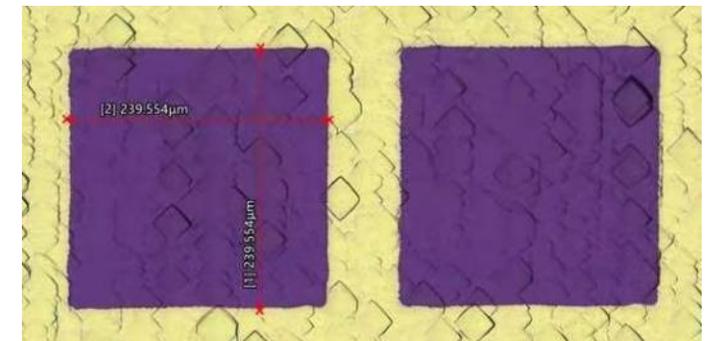
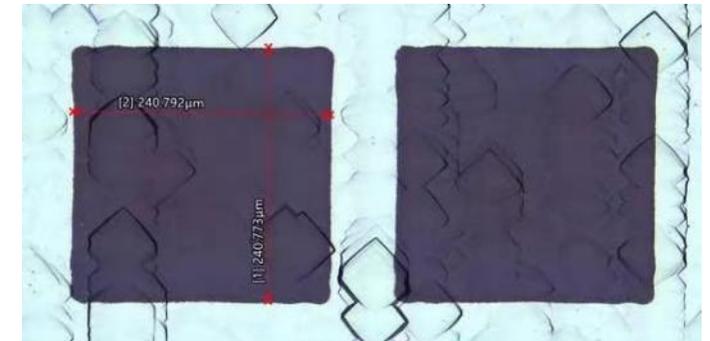
## Fine-tuning patternization

- Time-serial scanning control for well isolation of p- and n-type area
- AI algorithm introduced into visualization recognition for high alignment accuracy



## Flexible optimization of laser ablation

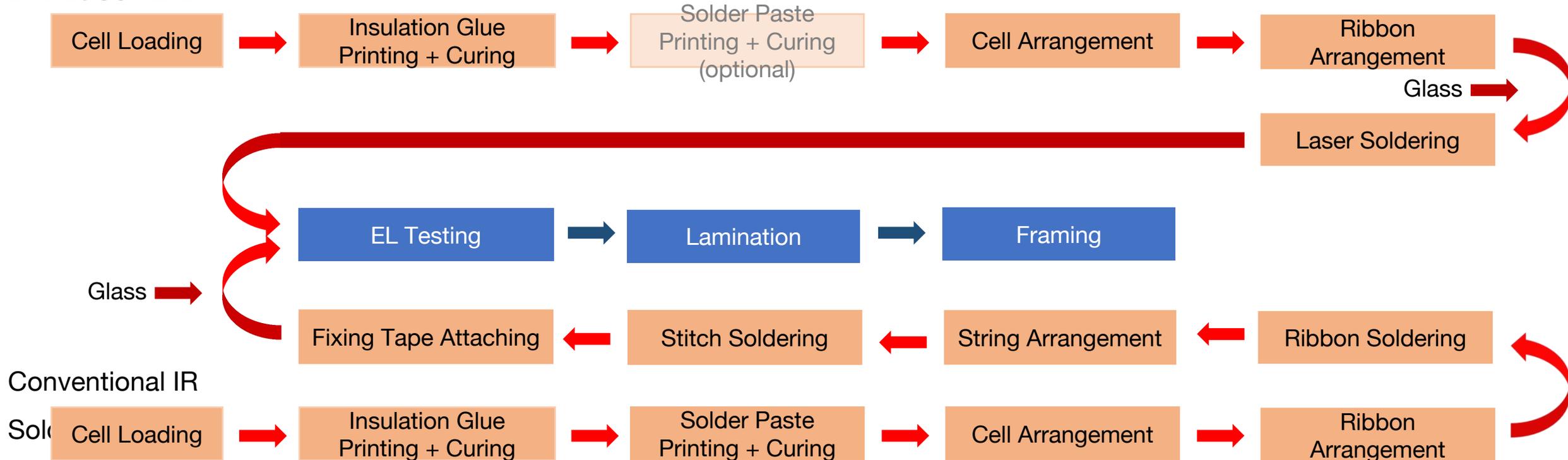
- Multiple models of laser sources suitable for the varied film
- Proven ablation processes for the varied XBC structure



# Cutting-Edge Laser Soldering Line for XBC Modules

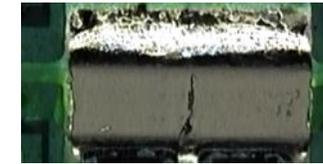
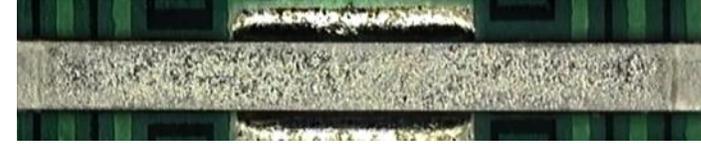


## DR Laser LIB



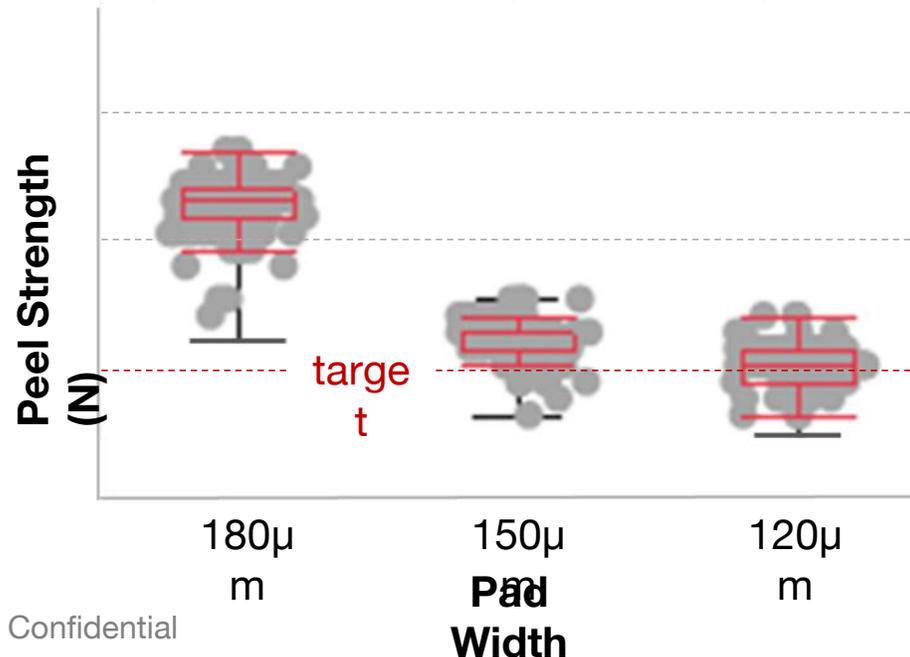
# Cutting-Edge Laser Soldering Line for XBC Module

- Low-temperature & local-heating process with high alignment accuracy
- No solder paste needed, complete soldering without pseudo soldering
- 0BB design compatible
- Ultra-thin wafer friendly due to ultra-low thermal stress
- Small footprint due to lean process sequence

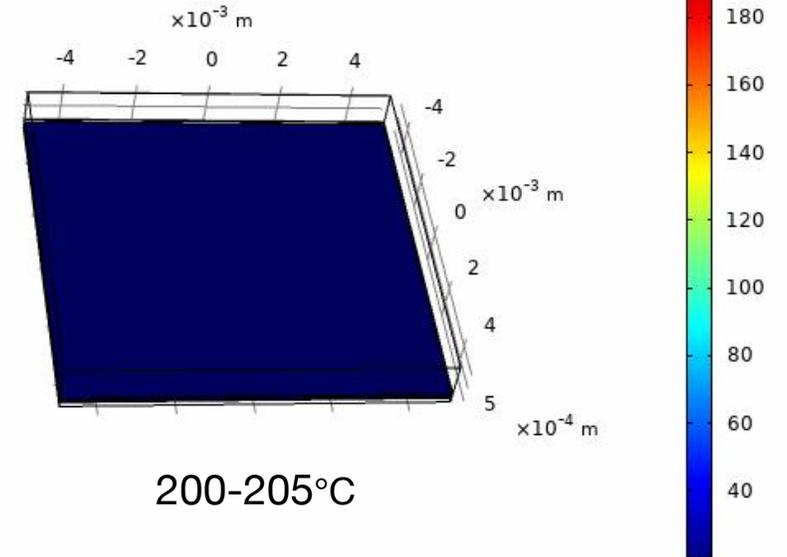
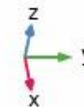


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DR Laser Confidential



# Q & A

